

Title (en)

METHOD FOR OBTAINING VANADIUM SLAG.

Title (de)

VERFAHREN ZUR HERSTELLUNG VON VANADIUMSCHLACKE.

Title (fr)

PROCEDE POUR L'OBTENTION DE LAITIER DE VANADIUM.

Publication

**EP 0235291 A4 19880120 (DE)**

Application

**EP 86900680 A 19850822**

Priority

SU 8500072 W 19850822

Abstract (en)

[origin: WO8701136A1] The vanadium slag contains the following components in per cent by weight: vanadium oxide 16-30, silicon oxide 10-24, manganese oxide 6-14, chromium oxide 1-12, titanium oxide 6-14, calcium oxide 0.3-30.0, metallic iron 2-20, iron oxide as the balance and has the following mineral composition in per cent by weight: spinellid 40-70; glass 2-10; pyroxenes and olivines representing balance. The grains of spinellid have a regular geometric shape and measure 25-80  $\mu\text{m}$ . The method of obtaining the vanadium slag of the composition mentioned provides for the use of vanadium cast iron containing, in per cent by weight: vanadium 0.35-0.90, carbon 3.8-4.8, silicon 0.05-0.35, manganese 0.12-0.35, titanium 0.07-0.38, chromium 0.03-0.42, phosphorus 0.02-0.10, copper 0.04-0.32, nickel 0.04-0.32, cobalt 0.001-0.12, iron being the balance. The above-named cast iron is blown through with a gaseous oxidizer, such as oxygen, at a blast intensity of 1.5-3.0  $\text{m}^2/\text{t}\cdot\text{min}$ , at a temperature of the cast iron at the beginning of blowing from 1,180 to 1,300°C and at the end of blowing from 1,400 to 1,650°C and with a specific area of the bath surface equal to 0.13 to 0.30  $\text{m}^2/\text{t}$ .

IPC 1-7

**C21C 5/36**

IPC 8 full level

**C21C 5/36** (2006.01)

CPC (source: EP)

**C21C 5/36** (2013.01)

Citation (search report)

- [A] DE 2810458 A1 19790920 - N PROIZV OB TULATSCHERMET
- [A] DE 2509650 A1 19760916 - TSNII TSCHERNOJ METALLURG IM I
- [A] FR 1598744 A 19700706
- [A] DE 3006287 A1 19811008 - SALZGITTER PEINE STAHLWERKE [DE]

Cited by

KR20020057680A; CN1068058C; RU2656125C2; WO9804750A1

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DE FR GB IT

DOCDB simple family (publication)

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JP S63500873 A 19880331

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